

Resist TWG Meeting

- Date: 2016-02-21
- Time: 8:30 AM
- Place:

Crystal Room
Fairmont San Jose
170 S. Market Street
San Jose, CA 95113

- Chair/contact: Yu-Jen.Fan@sematech.org

Agenda



Time	Title	Presenter
8:30 AM – 8:35 AM	Welcome and Opening	<i>Yu-Jen Fan, SUNY Poly SEMATECH</i>
8:35 AM – 8:50 AM	Recent progress in nanoparticle photoresist development for EUV lithography	<i>Kazuki Kasahara, JSR/Cornell</i>
8:50 AM – 9:05 AM	Recent development status of EUV rinse	<i>Tatsuro Nagahara, Merck</i>
9:05 AM – 9:15 AM	Accelerating Fab Integration of Metal Containing Resists	<i>Jason Stowers, Inpria</i>
9:15 AM – 9:30 AM	Advances in Alternative Photo Materials for HVM EUV Lithography	<i>Danilo De Simone, imec</i>
9:30 AM – 9:45 AM	Status update on outgassing of alternative resists	<i>Gijsbert Rispens, ASML</i>
9:45 AM – 10:00 AM	Update of Resist Outgas Testing at EIDEC	<i>Eishi Shiobara, EIDEC</i>
10:00 AM – 10:15 AM	Considerations for resist outgas testing with EUV and hydrogen at NIST	<i>Shannon Hill, NIST</i>
10:15 AM – 10:25 AM	IBM outgas update	<i>Dario Goldfarb, IBM</i>
10:25 AM – 10:45 AM	Coffee break / Social network	
10:45 AM – 11:00 AM	Fundamental aspects of sensitivity enhancement and RLS trade-off of chemically amplified EUV resist	<i>Seiichi Tagawa, Osaka University</i>
11:00 AM – 11:15 AM	Unconventional Organic High Resolution Resist Materials for EUV and E-beam Nanoscale Patterning: An Update	<i>Clifford Henderson, Georgia Tech</i>
11:15 AM – 11:30 AM	Molecular resists for EUV lithography	<i>Alex Robinson, Univ. of Birmingham</i>
11:30 AM – 11:45 AM	Is an EUV quantum yield of 30 possible?	<i>Greg Denbeaux, CNSE, SUNY Poly</i>
11:45 PM – 12:00 PM	What don't we know about the EUV exposure mechanisms?	<i>Robert Brainard, CNSE, SUNY Poly</i>
12:00 PM – 12:10 PM	Summary	<i>Yu-Jen Fan, SUNY Poly SEMATECH</i>

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